## Journal of Organometallic Chemistry, 105 (1976) C29–C31 © Elsevier Sequoia S.A., Lausanne – Printed in The Netherlands

### **Preliminary** communication

# GENERATION OF A VINYLIDENE CARBENE FROM AN $\alpha$ -CHLOROVINYLSILANE

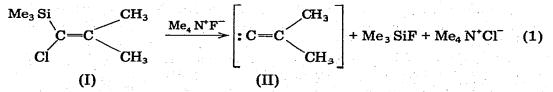
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#### Summary

The reaction of 1-chloro-1-trimethylsilyl-2-methylpropene with anhydrous tetramethylammonium fluoride in the presence of carbenophiles affords dimethylvinylidene insertion products.

The observation that fluoride ion serves as an effective reagent for the vicinal dehalosilylation of  $\beta$ -chlorovinylsilanes to acetylene [1] has been followed by applications to benzyne [2] and allene [3] syntheses. We now report a novel reactivity<sup>\*</sup> of 1-chloro-1-trimethylsilyl-2-methylpropene with anhydrous tetramethylammonium fluoride in which geminal dehalosilylation occurs to afford a vinylidene carbene (or carbenoid) species (II) (eq. 1)<sup>\*\*</sup>. The transformation is viewed as being initiated by nucleophilic attack of fluoride ion at silicon followed by loss of chloride ion from the incipient carbanionic center<sup>\*\*\*</sup>. Although potassium fluoride in aprotic solvents has proven a potent dechlorosilylating reagent for vicinal eliminations [1-3,8], it was ineffective for the present purpose. Evidence for the generation of II was provided by in situ trapping with the carbenophiles listed in Table 1.



The carbene precursor I was prepared as follows. To a mixture of 120 ml (180 mmol) of 1.5 N n-butyllithium in hexane, 265 ml of THF and 32 ml of

\*\*\*No evidence is yet at hand concerning the concertedness or non-concertedness of this process, or of the state of complexation of the resulting "carbene".

<sup>\*</sup>The thermolysis of  $\alpha$ -haloalkyltrihalosilanes is known to afford dihalocarbene (X<sub>2</sub> C:) species [5, 6]. Dichlorocarbene is also produced from the reaction of Cl<sub>3</sub> CP(O)(OEt)<sub>2</sub> with fluoride ion [7].

<sup>\*\*</sup>For other routes affording these species, see ref. 4.

Carbenophile	Product a	R	Yield (%) <sup>b</sup>	Reference
$\bigcirc$		CH3	55	12
$\checkmark$		СН3		
	CH3	OEt	66	12
CH==CH <sub>2</sub>		Ph	55	13
	R CH3	Me <sub>3</sub> Si	35	This work 9
•		CH3		
Et <sub>3</sub> SiH	Et <sub>3</sub> SiCH===C		65	14

<sup>a</sup> Also accompanied by 4-15% of 1-chloro-2-methylpropene. <sup>b</sup> Yields determined by GLC. <sup>c</sup> NMR (CDCl<sub>3</sub>, PhH int. std.)  $\delta$  1.63 (3H, s), 1.62 (3H, s), 0.96 (1H, m), 0.63 (1H, m), 0.40 (1H, m), -0.19 (9H, s). Found: C, 70.08; H, 11.70. C<sub>9</sub> H<sub>18</sub>Si calcd.: C, 70.05; H, 11.76%.

ether prepared at  $-100^{\circ}$ C was added 21 g (180 mmol) of N, N, N', N'-tetramethylethylenediamine (TMEDA) followed by precooled (-78°C) 1-chloro-2methylpropene (16 g, 180 mmol). After 4 h at -100°C, precooled (-78°C) trimethylchlorosilane (19 g, 180 mmol) and 10 ml of hexamethylphosphortriamide (HMPA)<sup>\*</sup> in 30 ml of THF were added in turn. The reaction mixture was held 1 h at  $-100^{\circ}$ C, 4 h at  $-78^{\circ}$ C and worked up by dilute acid and exhaustive water extraction. Fractionation afforded a forerun containing n-butyltrimethylsilane (26% by GLC)<sup>\*\*</sup>, followed by 11.3 g (39%) of  $I^{***}$ (91% pure by GLC), b.p. 160-162°C/760 mmHg. Refractionation gave material of 99% purity. Generation of the dimethylvinylidene insertion products can be illustrated by the reaction employing ethyl vinyl ether. Thus, a mixture of 0.95 g (5.8 mmol) of I, 0.57 g (6.2 mmol) of anhydrous Me<sub>4</sub> NF\*\*\*\*, 7.5 g (0.10 mmol) of ethyl vinyl ether and 10 ml of diglyme was prepared in a dry box. After two days at 25°C in a closed system, workup afforded a 66% yield of 2-ethoxy-1,1-isopropylidenecyclopropane and a 15% yield of 1-chloro-2-methylpropene, as determined by GLC. Trimethylfluorosilane was also identified as a reaction product. Total consumption of I occurred under these conditions.

The appearance of 1-chloro-2-methylpropene among the reaction products is presumably due to inherent<sup>\*\*\*\*</sup> and adventitious moisture present within the system which prevents carbene formation by protonation

<sup>\*</sup>A much lower yield of I is realized (ca. 10%) under similar conditions if HMPA is omitted. \*\*Optimization of metalation was not investigated. The literature contains references to un-

successful attempts at the metalation of 1-chloro-2-methylpropene [9].

<sup>\*\*\*</sup>IR: 3.35m, 6.21w, 6.95w, 7.31w, 8.0s, 11.2m, 11.96s, 13.24m  $\mu$ m; NMR (CCl<sub>4</sub>):  $\delta$  (ppm)

<sup>1.28 (9</sup>H, s), 1.87 (3H, s), 1.90 (3H, s). Found: C, 51.68, H, 9.47. C<sub>7</sub> H<sub>15</sub>ClSi calcd.: C, 51.67; H, 9.29%.

<sup>\*\*\*\*\*</sup>Prepared as reported [10] employing hydrogen fluoride dried over phosphorus pentafluoride [11]. Elemental analysis indicated a maximum water content of 11% for this material.

of I during or after silicon—carbon cleavage. In a separate experiment utilizing cyclohexene as the carbenophile, but employing a sample of anhydrous tetramethylammonium fluoride to which one equivalent of water had been added, a slow consumption of I occurred (72% over 75 h) which resulted in a 62% yield of 1-chloro-2-methylpropene and a 15% yield of insertion product.

It is worthy of note that the present system affords a mild method for the transfer of the dimethylvinylidene function which is unique in that the strongly basic conditions (alkoxide, organolithium reagents) usually employed in its generation are avoided.

## References

- 1 R.F. Cunico and E.M. Dexheimer, J. Amer. Chem. Soc., 94 (1972) 2868.
- 2 R.F. Cunico and E.M. Dexheimer, J. Organometal. Chem., 59 (1973) 153.
- 3 T.H. Chan and W. Mychajlowskij, Tetrahedron Lett., (1974) 171.
- 4 P.J. Stang, M.G. Mangum, D.P. Fox and P. Haak, J. Amer. Chem. Soc., 96 (1974) 4562.
- 5 W.I. Bevan and R.N. Haszeldine, J. Chem. Soc., Dalton Trans., (1974) 2509.
- 6 J.M. Birchall, G.N. Gilmore and R.N. Haszeldine, J. Chem. Soc., Perkin Trans. I, (1974) 2530.
- 7 J.P. Berry, J.R. Arnold and A.F. Isbell, J. Org. Chem., 33 (1968) 1664.
- 8 T.H. Chan and D. Massuda, Tetrahedron Lett., (1975) 3383.
- 9 G. Köbrich, Angew. Chem., Int. Ed. Eng., 11 (1972) 473.
- 10 G. Urban and R. Dötzer, U.S. Patent No. 3388131, June 11, 1968.
- 11 K.O. Christe, C.J. Schaak and R.D. Wilson, Inorg. Chem., 14 (1975) 2224.
- 12 H.D. Hartzler, J. Amer. Chem. Soc., 86 (1964) 526.
- 13 M.S. Newman and T.B. Patrick, J. Amer. Chem. Soc., 91 (1969) 6461.
- 14 A.D. Petrov and G.I. Nikishin, Zh. Obshch. Khim., 26 (1956) 1233; M.S. Newman and C.D. Beard, J. Amer. Chem. Soc., 92 (1970) 4309.